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(71) Applicant (for all designated States except US): KAO
CORPORATION [JP/JP]; 14-10, Nihonbashi Kayabacho
1-chome, Chuo-ku, Tokyo 103-8210 (JP).

(72) Inventors; and

(75) Inventors/Applicants (for US only): YONEDA, Yasuhiro
[JP/JP]; Kao Corporation, Research Laboratories,

1334, Minato, Wakayama-shi, Wakayama 640-8580
(JP). HASHIMOTO, Ryoichi [JP/JP]; Kao Corporation,
Research Laboratories, 1334, Minato, Wakayama-shi,
Wakayama 640-8580 (JP). HAGIHARA, Toshiya [JP/JP];
Kao Corporation, Research Laboratories, 1334, Minato,
Wakayama-shi, Wakayama 640-8580 (JP).

(74) Agent: HOSODA, Yoshinori; Hosoda International
Patent Office, Otemae M2 Bldg., 8-1, Tanimachi 2-chome,
Chuo-ku, Osaka-shi, Osaka 540-0012 (JP).

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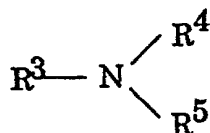
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(54) Title: POLISHING LIQUID COMPOSITION



(II)

prising an amine compound represented by general formula (II) wherein R³ is a linear or branched alkyl group having 4 to 18 carbon atoms, a linear or branched alkenyl group having 4 to 18 carbon atoms, an aryl group having 6 to 18 carbon atoms, and an aralkyl group having 7 to 18 carbon atoms; each of R⁴ and R⁵, which may be identical or different, is hydrogen atom, a linear alkyl group having 1 to 8 carbon atoms or a branched alkyl group having 3 to 8 carbon atoms, or a group represented by H-(OR⁶)_Z, wherein R⁶ is a linear alkylene group having 1 to 3 carbon atoms, or a branched alkylene group having 3 carbon atoms; and Z is a number of 1 to 20, and/or a salt thereof, an etching agent, and water.

(57) Abstract: A polishing liquid composition for polishing a surface to be polished comprising an insulating layer and a metal layer selected from (1) to (3): (1) the polishing liquid composition comprising a compound having a structure in which each of two or more adjacent carbon atoms has a hydroxyl group in a molecule, and water; (2) the polishing liquid composition comprising an aliphatic carboxylic acid having 7 to 24 carbon atoms and/or a salt thereof, an etching agent, and water; (3) the polishing liquid composition com-

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